

Recipe for photoresist AZ 5214E

Application

Substrate preparation: It is preferable to process the silicon substrate by evaporation of HMDS at 150°C for 45 seconds, using the Delta RC80.

Process

Tone	Positive
Special	Image Reversal
Reference	Merck
Spin coat	1.5 μm @4000 RPM
Pre bake	1 min @105°C (+10°C 5" wafer) on hotplate
Exposure time	7 sec @7.96 mW/cm ²
Development	60 sec in MF321
Stopping of development	30 sec in H ₂ O

Results

Spin curve

